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Applicant(s): Yoshinori NISHIWAKI et al.			
Serial No. 10/532,364	Filing Date April 20,2005	Examiner To Be Assigned	Group Art Unit To Be Assigned
Invention: CHEMICALLY AMPLIFIED POSITIVE PHOTOSENSITIVE RESIN COMPOSITION			
			
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(54) POSITIVE TYPE PHOTORESIST COMPOSITION, BOARD WITH
PHOTOSENSITIVE FILM AND RESIST PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a positive type photoresist composition capable of forming a space pattern excellent in heat resistance with good acid generation efficiency under a thick film condition of $\geq 3.0 \mu\text{m}$ and capable of forming a space pattern having $\leq 0.8 \mu\text{m}$ width and a high aspect ratio with good perpendicularity and to provide a board with a photosensitive film and a resist pattern forming method.

SOLUTION: The positive type photoresist composition contains an alkali- soluble novolak resin in which part of the hydrogen atoms of all hydroxyl groups have been substituted by 1,2-naphthoquinonediazidosulfonyl groups and an acid generating agent.

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